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Published in:
IEEE Transactions on Components, Packaging and Manufacturing Technology

Link to article, DOI:
10.1109/TCPMT.2019.2928053

Publication date:
2019

Document Version
Peer reviewed version

Link back to DTU Orbit

Citation (APA):
System Integration and Packaging of a Terahertz Photodetector at W-Band

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Abstract—This paper presents the system integration and packaging of a photodetector at W-band (75-110 GHz) for terahertz (THz) communications. The ErAs:In(Al)GaAs photodetector and its feeding network based on semi-insulating indium phosphide (InP) substrate are introduced. The design of the bias-tee at W-band is described and the effect of parasitic modes is discussed. Besides, the transition using E-plane probe between a W-band rectangular waveguide (WR-10) and a coplanar waveguide (CPW) is illustrated. The bias-tee as well as the E-plane probe transition are based on high-resistivity silicon (Si) substrate where wire bonding bridges are added on the top following the CPWs in order to restrict parasitic modes. The integration approach and the packaging structure are addressed. The proposed bias-tee and the E-plane probe transition including the WR-10 rectangular waveguide are fabricated, integrated, and measured. The measurement is carried out on-wafer in a back-to-back configuration and the results are presented. The assembly of the fully-packaged photodetector is demonstrated and an THz heterodyne communication system is implemented which validates the proposed system integration and packaging approach of the photodetector at W-band.

Index Terms—Bias-Tee, coplanar waveguide (CPW), E-plane probe, integration, packaging, photodetector, terahertz (THz), rectangular waveguide, wire bonding.

I. INTRODUCTION

WITH the fast development of lightwave systems and the increasing demand for high-speed data transmissions through not only optical fibers over a long distance but also wireless links to mobile terminals [1]–[4], terahertz (THz) photodetectors as one of the principal devices used in communication systems are under intensive study. As the optoelectronic devices that can convert signals from optical domain to electrical domain, photodiodes as well as photoconductors operating at THz frequencies have been pushed to achieve larger bandwidths [5]–[9]. Though both components can be implemented into photodetectors, they are based on different electro-optic effects which result in different characteristics. By adding an undoped region in a semiconductor junction, the photodiodes work as a rectifier converting light photons into an alternating current (AC). For the photoconductors, with a direct current (DC) bias its resistance is related to the number of free carriers in the photoconductive material generated by the light photons. At millimeter-wave and THz frequencies, not only the components but also the strategies for system integration and packaging are being challenged and efforts have been put to improve the performances [10]–[15]. Fig. 1 shows the system diagram of the THz photodetector as a part of the transmitter (Tx) used for wireless data transmissions at W-band. Instead of directly using a log-periodic antenna with a silicon lens [16], the photoconductor is integrated with other components and packaged inside a rectangular waveguide structure which allows the photodetector being cascaded with the amplifiers as well as the horn antenna in the system.

In THz communication systems, as one of the possible methods, a laser can be used as the light source and the data is modulated to the optical carrier by using a Mach-Zehnder modulator (MZM). After that, the modulated optical signal is transmitted to the photodetector through an optical fiber which needs to be aligned accurately with the photoconductor. The photoconductor is attached to a feeding network and the radio frequency (RF) signal is generated by the photoconductor based on the optical input. Alternatively, depending on the modulation scheme of the communication system, not only the DC bias but also the intermediate frequency (IF) signal might have to be provided to the photoconductor. As a consequence, a bias-tee is connected to the feeding network and chip-level
connections between them are required. The bias-tee is a three-port component based on planar transmission lines where the RF signal is transmitted freely towards the connected component while the DC bias and IF signal can only be guided to the photoconductor [17]. Since a rectangular waveguide serves as the interface of the packaging structure, a transition based on planar transmission lines is inserted for guiding the RF signal from the bias-tee to the rectangular waveguide. Besides, the rectangular waveguide isolates the DC bias as well as the IF signal so that the DC block can be avoided in the packaging structure. The organization of the paper is as follows. In Section II, the designs of feeding network, bias-tee, and transition are described. The fabrication, integration, and packaging of the components are addressed. In Section III, the assembly of the fully-packaged photodetector is demonstrated. Besides, a THz heterodyne communication system is implemented and the measurement results are presented. Conclusions are finally drawn in Section IV.

II. PACKAGING CONSIDERATIONS

A. Feeding Network

In order to guide the RF signal generated by the photoconductor to the bias-tee and the IF signal together with the DC bias to the photoconductor, a transmission line feed is implemented. A coplanar waveguide (CPW) is used due to its simple planar structure, tunable dimension, and low dispersion loss in a wide frequency range. Fig. 2 shows the proposed CPW feed based on a semi-insulating indium phosphide (InP) substrate, which has a thickness of 350 µm. The dielectric constant (εr) and dissipation factor (tanδ) of the InP substrate are 12.56 and 2e-4, respectively [18]. Gold is used as the material of the conductor layer and its thickness is 200 nm. The metal carrier under the InP substrate also works as the bottom ground plane. The CPW is designed to have a characteristic impedance of 50 Ω which supports not only DC bias but also low-loss transmissions up to 110 GHz. The width of the signal trace is 50 µm and the width of the ground traces is 300 µm with a gap of 50 µm. For aligning the photoconductor, the width of the signal trace is tapered to 8 µm at the end while the ground traces are merged into a ground pad. The distance between the signal trace and the ground pad is 6 µm. Besides, wire bonding bridges on the top of the substrate are implemented along the CPW which are used for restricting parasitic modes. The height of the wire bonding bridges is 50 µm and they are placed 160 µm from each other. In the simulation, lumped ports are used as the excitation scheme and the photoconductor is represented by a port which is assigned to a surface located in the gap between the signal trace and the ground pad.

Fig. 3 shows the simulation results of the CPW feed based on InP substrate with wire bonding bridges in comparison with the situation when wire bonding bridges are removed. Due to the simple through line structure of the CPW feed and a length of 680 µm, similar performances are achieved and no visible notch is observed up to 110 GHz. In both cases, the return loss remains better than 17 dB and the insertion loss is less than 0.5 dB.

B. Bias-Tee

As is illustrated in Fig. 4, a bias-tee is designed for guiding the RF signal from the connected feeding network to the following transition while bringing the DC bias as well as the IF signal to the photoconductor at the same time. Since the bias-tee is a three-port component, except for supporting low-loss transmissions at W-band, it is also important to provide a good isolation for the RF signal so that it will be guided solely along the RF path. Besides, due to the rectangular waveguide involved in the packaging structure, the DC block on the RF path in order to prevent the DC bias from being brought to the following components can be avoided. By taking into account the feeding network as well as the transition, the bias-tee is realized using CPWs based on a high-resistivity silicon (Si) substrate which has a thickness of 280 µm. The εr and tanδ of the Si substrate are 11.6 and 4e-3, respectively [19].

The RF path consists of a CPW through line with a length of 1 mm. The characteristic impedance is 50 Ω. For easier integration with the feeding network, the signal trace is designed to have an identical width which is 50 µm. The DC/IF path is connected to the RF path in the middle and the width of the signal trace is optimized to 20 µm. In both cases, the gap between the signal and ground traces is 30 µm. In order to prevent the RF signal from leaking to the DC/IF path, two open-circuited CPW stubs are implemented in parallel. Fig. 5 demonstrates the equivalent schematics of the proposed
bias-tee and the corresponding impedance transformations on the Smith chart. The original idea for designing the bias-tee is to implement a through line structure on the RF path and a quarter-wavelength transformer on the DC/IF path which converts the termination from short to open. In this case, a quarter-wavelength CPW is followed by a half-wavelength CPW short-circuited stub. Though the RF signal can be isolated from the DC/IF path, the DC bias is directly short-circuited by the stub. As an alternative, the half-wavelength CPW short-circuited stub is replaced by a quarter-wavelength CPW open-circuited stub. In addition, another identical open-circuited stub is added in parallel which further improves the isolation for the RF signal and at the same time, it does not increase the occupation area of the bias-tee.

Based on the second schematic shown in Fig. 5, the bias-tee is designed and the dimensions are optimized for the RF signal at W-band. For restricting parasitic modes, wire bonding bridges on the top of the substrate are also added along the paths. In the simulation, lumped ports with vertical perfect electric conductor (PEC) bridges are used as the excitation scheme. Fig. 6 shows the simulation results of the proposed bias-tee based on Si substrate with wire bonding bridges. The return loss is better than 16.6 dB with an associated insertion loss of 0.9 dB. Besides, the simulated isolation for the RF signal is more than 18.6 dB. In contrast, for the situation when wire bonding bridges are removed, the performance of the bias-tee degrades dramatically due to parasitic modes.

C. Rectangular Waveguide-to-CPW Transition

With an interface of rectangular waveguide, the RF signal generated by the photoconductor can be easily connected to other devices at the output of the photodetector. Since both the feeding network and the bias-tee are based on CPWs, the transition becomes an essential component in the packaging structure. Several different types of rectangular waveguide-to-CPW transitions can be found in the literature [20]–[25] while E-plane probe exhibits noticeable performances especially at millimeter-wave and submillimeter-wave frequencies [26]–[29]. Fig. 7 shows the proposed transition at W-band using E-plane probe. A rectangular patch patterned on a high-resistivity Si substrate works as the E-plane probe which is inserted into the WR-10 rectangular waveguide through an aperture cut in the center of the broadwall parallel to the longitudinal axis. The E-plane probe is placed 740 μm from the end of the rectangular waveguide which forms a quarter-wavelength transformer converting the termination from short to open. In order to guide the RF signal from the bias-tee to the E-plane probe smoothly, a CPW is included in the transition structure which has a length of 1 mm and a characteristic impedance of 50 Ω. Though the CPW is patterned on the same substrate, its dimensions are optimized for the new environment conditions due to the metal cover around the transition. In addition, efforts are put to restrict parasitic modes by adding wire bonding bridges, reducing the width of the substrate as well as the height of the cavity. As a result, the width of the signal trace is 80 μm and the width of the ground traces is 110 μm with a gap of 50 μm. For easier integration with the bias-tee, the CPW is tapered at the beginning.

In the simulation, the length of the rectangular waveguide is set to 10 mm and wave ports are used as the excitation scheme. The rounded corners at the end of the rectangular waveguide are also included for being compatible with the milling process which results in a radius of 250 μm. Fig. 8 shows the simulation results of the proposed E-plane probe transition at W-band. With wire bonding bridges, the E-plane probe transition based on Si substrate exhibits a wideband
Based on the system diagram shown in Fig. 1, the individual components are integrated and chip-level connections are implemented. Fig. 9 demonstrates the proposed approach for integrating the feeding network, bias-tee, and E-plane probe transition. A metal carrier is used for realizing the WR-10 rectangular waveguide, packaging the E-plane probe transition, and providing physical support for other components. By milling the metal carrier into several platforms, the thickness difference between the InP and Si substrates can be compensated. As a result, the components are aligned by their top surfaces so that the vertical gap is avoided at the connections. In addition, wire bondings with a diameter of 25 \( \mu \text{m} \) are used for not only chip-level connections but also providing ground connections to the components at different positions on the substrates. Since the wire bonding connections introduce parasitic inductance especially at high frequencies, the components are placed as close as possible and the height of the wire bondings is kept around 50 \( \mu \text{m} \).

The bias-tee is optimized from the original design for an easier integration. On the RF path, by reducing the width from 300 \( \mu \text{m} \) to 145 \( \mu \text{m} \), the ground trace touches the metal carrier and it is aligned to the edge of the transition at the same time. By taking into account the DC bias as well as the potential IF signal, the signal trace is extended in order to reach the inputs which are connected to the bias-tee through a SMA connector at the far end. With the purpose of enlarging the bandwidth of the potential IF signal, an impedance transformer based on microstrip line is inserted to the DC/IF path whose width and length are 550 \( \mu \text{m} \) and 2 mm, respectively. After that, a microstrip line with a characteristic impedance of 50 \( \Omega \) is implemented for guiding the potential IF signal. The width is 200 \( \mu \text{m} \) and the length is 15.685 mm. At the end of the DC/IF path, there is a square pad with a length of 400 \( \mu \text{m} \) which is large enough for connecting to the SMA connector. In order to be compatible with the experimental setup at W-band, the WR-10 rectangular waveguide is bent 90° with a total length of approximately 25 mm. For minimizing the reflection, the quadrant structure has an inner radius of 1 mm and it is placed 4 mm from the end of the rectangular waveguide.

In the simulation, different types of excitation schemes are used. A lumped port is assigned to a surface located in the gap between the signal trace and the ground pad on the feeding network. It represents the photoconductor and is used as the input of the RF signal as well as the output of the IF signal. A wave port is assigned to the outer surface of the rectangular waveguide which is the output of the RF signal. As for the input of the IF signal, another lumped port is assigned to the surface between the square pad on the bias-tee and the bottom metal carrier. The simulation results of the integrated components for both RF and IF signals are shown in Fig. 10. Since the RF signal operates at W-band, the simulation results range from 75 GHz to 110 GHz. The return loss remains better than 15 dB with an associated insertion loss of 2.3 dB and the isolation is more than 16 dB. However, the IF signal is
simulated up to 10.5 GHz. It achieves a return loss of 10 dB and an associated insertion loss of 1 dB up to 3 GHz while they reach 7.7 dB and 2 dB, respectively, at 10 GHz.

E. Fabrication and Experimental Results

In order to prove the designs and validate the proposed integration approach, the bias-tee, E-plane probe transition, and WR-10 rectangular waveguide demonstrated in Fig. 9 were fabricated. The bias-tee and E-plane probe transition were patterned on an n-type high-resistivity Si wafer which has a diameter of 50.8 mm and a crystal orientation of $<100>$. At the beginning, a conductor layer was deposited on the top of the Si wafer with a thickness of 200 nm using gold evaporation. After that, different layouts were patterned by following the process of photolithography. The wafer was diced into samples which were integrated into two identical prototypes at the end. Fig. 11 shows the integration of the fabricated bias-tee and E-plane probe transition. The metal package including the rectangular waveguide was divided into two parts and each part was fabricated using a brass block by milling process which was carried out by using a spinner with a radius of 250 μm. For accurate assembly, guide pins as well as screws were used and a standard WR-10 rectangular waveguide flange with annular recess was also applied to the fabricated brass package. The bias-tee and E-plane probe transition were first aligned on the brass carrier and the gaps were filled with silver epoxy. Then the wire bonding bridges along the CPWs, wire bonding connections between the components, and ground connections at different positions were added by ball bonding process. The brass cover was assembled at the last step.

Fig. 12 illustrates the experimental setup for on-wafer measurement at W-band as well as the device under test (DUT). The experimental setup comprises an Anritsu ME7808B vector network analyzer (VNA), two WR-10 extenders from Anritsu, and two ground-signal-ground (GSG) probes with a pitch size of 125 μm. The DUT has a back-to-back configuration which consists of two identical prototypes connecting to each other through the rectangular waveguide flanges.

By applying the GSG probes to the integrated bias-tees of the prototypes, two-port S-parameters were measured at W-band and on-wafer calibration was executed before the measurement. Fig. 13 shows both the measurement and the simulation results of the integrated bias-tee and transition in a back-to-back configuration. From 75 GHz to 110 GHz, the measured return loss remains better than 9.4 dB with an associated insertion loss of 8.6 dB. As a result, each prototype introduces less than 4.3 dB insertion loss at W-band. Compared with the simulation results, an extra insertion loss of 2.7 dB is achieved by each prototype which is mainly caused by the integration process especially the wire bonding connections between the components and the tanδ variation of the Si substrate at such high frequencies. From the system integration point of view, a measured return loss of 9.4 dB is acceptable while the insertion loss can be compensated to some extend by the cascaded W-band amplifiers in the communication system.

III. SYSTEM INTEGRATION

A. Fully-Packaged Photodetector

Though the integration of the feeding network, bias-tee, and E-plane probe transition has been addressed, the photoconductor as well as other supplementary components such as optical fibers, connectors, and outer metal covers are also necessary in order to have a fully-packaged photodetector. At telecom
wavelengths, the photoconductor is challenged by finding suitable photconductive materials with a short carrier lifetime. Due to the low dark resistance, the DC bias that can be applied to the photoconductor is normally limited which makes it difficult to achieve a sufficient output power. According to [8], by combining erbium arsenide (ErAs), indium gallium arsenide (InGaAs), and indium aluminium arsenide (InAlAs) layers, the fabricated photoconductor exhibits excellent THz performances with a high dark resistance under continuous wave (CW) operations. As a result, the ErAs:InAlGaAs photoconductor is packaged into a THz photodetector which is used as a part of the transmitter in the communication system.

Fig. 14 illustrates the assembly of the fully-packaged photodetector. Apart from the principal components, a SMA connector inserting through the sidewall of the brass package was connected to the DC/IF path on the bias-tee and an angled physical contact (APC) connector with an optical fiber was used for guiding the optical signal all the way to the photoconductor. Since the optical signal needs to be illuminated to the photoconductor from the top, by taking into account the efficiency as well as accuracy, a fiber holder with customized dimensions was employed. The fiber holder was fabricated using a polyvinyl chloride (PVC) block by milling process and the optical fiber was fixed inside a though hole drilled from the top. Besides, the outer metal covers made from brass plates were added so that a fully-packaged device is set up with both physical and electrical protections.

B. Experimental Setup and Results

In order to validate the proposed system integration and packaging approach of the photodetector, the THz heterodyne communication system demonstrated in Fig. 15 is implemented. On the transmitter (Tx) side, a CW laser operating at 1550 nm is used as the light source and a polarization controller (PC) is added before the optical signal reaches the MZM where a RF signal at local oscillator frequency ($f_{LO}$) is modulated to the optical signal achieving two optical tones with the expected distance ($2f_{LO}$) in the spectrum. Then an erbium-doped fiber amplifier (EDFA) is employed to enlarge the power of the optical signal and followed by an arrayed waveguide grating (AWG) which demultiplexes the two optical tones. The data is modulated to one of the tones by using another MZM and a variable optical attenuator (VOA) is applied on the other tone which adjusts the power of the optical signal. After that, the two optical tones are coupled together and the spectrum of the optical signal is also presented. Another EDFA pushes up the power of the optical signal to 30 mW before being transmitted to the photodetector. The RF signal with the modulated data has a frequency component of $2f_{LO}$ which is generated by the photodetector and then guided to a low noise amplifier (LNA) followed by a medium power amplifier (MPA). The W-band LNA and MPA from Radiometer Physics GmbH can provide gains of 40 dB and 10 dB, respectively. For radiating the RF signal into free space, a W-band standard horn antenna is used which has a gain of 21 dB.

On the receiver (Rx) side, a comb fiber laser operating at 1550 nm is used as the light source and the repetition rate ($f_{comb}$) is 40 GHz. The generated optical frequency comb goes through a wavelength selective switch (WSS) which reserves the two optical tones with a distance of 80 GHz ($2f_{comb}$) in the spectrum and the rest of the tones are suppressed. The power of the filtered optical signal is increased to 30 mW by using an EDFA and the spectrum is also shown in Fig. 15. The photodetector is based on an ErAs:InGaAs photoconductor which is attached to a log-periodic antenna and packaged using a hemispherical silicon lens. Since the DC bias is not required by the photoconductor in this case, the InAlAs layer is excluded, which according to [8] provides a higher mobility and a better sensitivity compared with the photoconductor used on the Tx side. When the IF signal is extracted by the photodetector, it has a frequency component of $|2f_{comb} - 2f_{LO}|$ which can be tuned by sweeping the $f_{LO}$ on the Tx side. Besides, a transimpedance amplifier (TIA) and two electrical amplifiers (EAs) are employed which provide
The authors would like to thank S. Schober and T. Schildknecht at the Department of Electrical Engineering and Information Technology, Technische Universität Darmstadt for assisting the fabrication processes.

REFERENCES


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